

MIXING APPARATUS OF CHEMICAL FOR SEMICONDUCTOR

Publication number: JP61118127 (A)

Publication date: 1986-06-05

Inventor(s): WADA ATSUKI; NUMATA SEIICHI; TAKADA HITOO

Applicant(s): KURASHIKI BOSEKI KK

Classification:

- international: **B01F15/04; B01F3/08; B01F15/02; B01J4/00; B01J4/02;**
B01F15/04; B01F3/08; B01F15/02; B01J4/00; B01J4/02; (IPC1-
7): B01F15/02; B01F15/04

- European: B01F3/08P; B01J4/00

Application number: JP19840239644 19841113

Priority number(s): JP19840239644 19841113

Also published as:

JP5079372 (B)

JP1863802 (C)

Abstract of JP 61118127 (A)

PURPOSE: To reduce the contamination by foreign matter and to obtain homogeneous composition by providing a means for sucking a liq. in a mixing vessel and a filter means for removing foreign matter in the liq., and furnishing a circulating passage for circulating the liq. in the mixing vessel through the means. **CONSTITUTION:** Hydrogen peroxide soln. is supplied to the second mixing vessel 87 housed in the second storage vessel 22 by using high-pressure gas as the driving source through a branch pipe 51b from a liq. feed pipeline 51 on the opening and closing valve 88 side, a spiral pipe, and an inlet pipe. Sulfuric acid is simultaneously supplied from the third storage vessel 23 through a liq. feed pipe 91 having an opening and closing valve 90, the respective supplies are measured by a platform balance 92, and both chemicals are mixed in a specified ratio.; The liq. mixture is circulated through the inside of a circulating passage 96 including a circulated and delivery pump 93, a liq. filter 94, and a heat exchanger 95, and the agitation, filtration, and temp. regulation are carried out.

